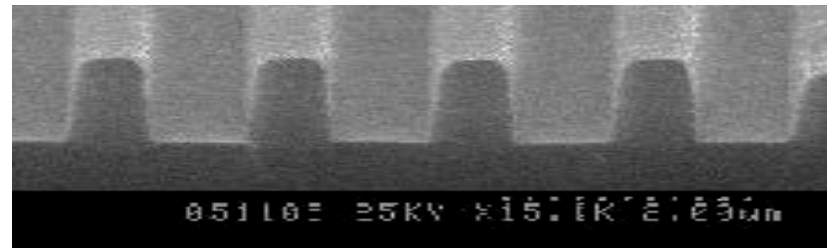


# Mask Aligner

- The Karl Suss MA6 high-resolution photolithography mask aligner is located in the Class-100 cleanroom and is designed to image patterns on wafers up to 6 inches in size.
- A 350W mercury short-arc lamp is typically used for exposure in the wavelengths of 350-500nm (nanometers).
- A line/space resolution of 1.0 micron and a high precision alignment stage which allows alignment accuracy to 0.1 microns can be obtained under optimal conditions.
- The aligner has four exposure modes: vacuum contact, hard contact, soft contact, and proximity.



1.0 um lines/spaces